

Title: Sub-micron structuring of silicon using femtosecond laser interferometry

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Source: Optics and Laser Technology **Volume:** 54

Pages: 428-431 **DOI:** 10.1016/j.optlastec.2013.06.031 **Published:** Dec 30 2013

Document Type: Article

Language: English

Abstract: We report the fabrication of planar sub-micron gratings in silicon with a period of 720 nm using a modified Michelson interferometer and femtosecond laser radiation. The gratings consist of alternated stripes of laser ablated and unmodified material. Ablated stripes are bordered by parallel ridges which protrude above the unmodified material. In the regions where ridges are formed, the laser radiation intensity is not sufficient to cause ablation. Nevertheless, melting and a significant temperature increase are expected, and ridges may be formed due to expansion of silicon during resolidification or silicon oxidation. These conclusions are consistent with the evolution of the stripes morphology as a function of the distance from the center of the grating. (C) 2013 Elsevier Ltd. All rights reserved.

Author Keywords: Silicon patterning; Femtosecond laser; Michelson interferometer

KeyWords Plus: Fabricaton; Ablation; Pulses; Si; Interference; Surfaces; Gratings; Lithography; Solids; Arrays

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Funding:

| Funding Agency | Grant Number |
|--|---|
| Portuguese Foundation for Science and Technology (FCT) | PTDC/FIS/121588/2010 SSFRH/BPD 17382712010 |

Publisher: Elsevier SCI LTD

Publisher Address: The Boulevard, Langford Lane, Kidlington, Oxford OX5 1GB, Oxon, England

ISSN: 0030-3992

Citation: OLIVEIRA, V.; VILAR, R.; SERRA, R.; OLIVEIRA, J. C.; POLUSHKIN, N. I.; CONDE, O. - Sub-micron structuring of silicon using femtosecond laser interferometry. Optics and Laser Technology. ISSN 0030-3992. Vol. 54 (2013), p. 428-431.